

# Larissa Juschkin

## List of Publications by Year in descending order

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75  
papers

609  
citations

623734

14  
h-index

713466

21  
g-index

79  
all docs

79  
docs citations

79  
times ranked

443  
citing authors

#	ARTICLE	IF	CITATIONS
1	High speed imaging of Z-pinch gas discharge in extreme ultraviolet and model-based three-dimensional reconstruction of emitting volume. Review of Scientific Instruments, 2022, 93, 013503.	1.3	3
2	Extreme ultraviolet free-standing transmittance filters for high brilliance sources, based on Nb/Zr and Zr/Nb thin films on Si <sub>3</sub> N <sub>4</sub> membranes: Design, fabrication, optical and structural characterization. Thin Solid Films, 2020, 695, 137739.	1.8	2
3	Quantitative characterization of absorber and phase defects on EUV reticles using coherent diffraction imaging. Journal of Micro/ Nanolithography, MEMS, and MOEMS, 2020, 19, 1.	0.9	11
4	Computational proximity lithography with extreme ultraviolet radiation. Optics Express, 2020, 28, 27000.	3.4	3
5	On space charge effects in laboratory-based photoemission electron microscopy using compact gas discharge extreme ultraviolet sources. New Journal of Physics, 2020, 22, 103019.	2.9	3
6	Spatially Resolved Spectroscopic Extreme Ultraviolet Reflectometry for Laboratory Applications. Journal of Nanoscience and Nanotechnology, 2019, 19, 562-567.	0.9	2
7	Optical and structural characterization of orthorhombic LaLuO <sub>3</sub> using extreme ultraviolet reflectometry. Thin Solid Films, 2019, 680, 94-101.	1.8	1
8	A scanning reflection X-ray microscope for magnetic imaging in the EUV range. Journal of Synchrotron Radiation, 2019, 26, 2040-2049.	2.4	1
9	Fast and easy fabrication methodology of Fresnel zone plates for the extreme ultraviolet and soft x-ray regions. Applied Optics, 2019, 58, 1057.	1.8	5
10	EUV-LET 2.0: a compact exposure tool for industrial research at a wavelength of 13.5nm. , 2019, , .		3
11	Structural properties of templated Ge quantum dot arrays: impact of growth and pre-pattern parameters. Nanotechnology, 2018, 29, 275601.	2.6	5
12	Holographic masks for computational proximity lithography with EUV radiation. , 2018, , .		1
13	Ptychographic imaging with partially coherent plasma EUV sources. Advanced Optical Technologies, 2017, 6, 459-466.	1.7	1
14	Optimized phase-shifting masks for high-resolution resist patterning by interference lithography. , 2017, , .		2
15	Compact extreme ultraviolet source for laboratory-based photoemission spectromicroscopy. Applied Physics Letters, 2016, 108, .	3.3	8
16	Deposition and characterization of B <sub>4</sub> C/CeO <sub>2</sub> multilayers at 6.x nm extreme ultraviolet wavelengths. Journal of Applied Physics, 2016, 119, .	2.5	2
17	Lloyd's mirror interference lithography with EUV radiation from a high-harmonic source. Applied Physics Express, 2016, 9, 076701.	2.4	6
18	Achromatic Talbot lithography with partially coherent extreme ultraviolet radiation: process window analysis. Journal of Micro/ Nanolithography, MEMS, and MOEMS, 2016, 15, 043502.	0.9	19

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19	Enabling laboratory EUV research with a compact exposure tool. Proceedings of SPIE, 2016, , .	0.8	3
20	Restorative Self-Image of Rough-Line Grids: Application to Coherent EUV Talbot Lithography. IEEE Photonics Journal, 2016, 8, 1-9.	2.0	7
21	Freeform lens collimating spectrum-folded Hadamard transform near-infrared spectrometer. Optics Communications, 2016, 380, 161-167.	2.1	7
22	Laser-assisted vacuum arc extreme ultraviolet source: a comparison of picosecond and nanosecond laser triggering. Journal Physics D: Applied Physics, 2016, 49, 225201.	2.8	13
23	Lensless Proximity EUV Lithography with a Xenon Gas Discharge Plasma Radiation. Springer Proceedings in Physics, 2016, , 313-319.	0.2	1
24	Single Exposure Imaging of Talbot Carpets and Resolution Characterization of Detectors for Micro- and Nano- Patterns. Journal of the Optical Society of Korea, 2016, 20, 245-250.	0.6	3
25	Coherent Diffractive Imaging with a Laboratory-Scale, Gas-Discharge Plasma Extreme Ultraviolet Light Source. Springer Proceedings in Physics, 2016, , 275-280.	0.2	0
26	Optical properties of 2D fractional Talbot patterns under coherent EUV illumination. Journal Physics D: Applied Physics, 2015, 48, 375101.	2.8	7
27	Multi-angle spectroscopic extreme ultraviolet reflectometry for analysis of thin films and interfaces. Physica Status Solidi C: Current Topics in Solid State Physics, 2015, 12, 318-322.	0.8	9
28	A phase retrieval algorithm based on three-dimensionally translated diffraction patterns. Europhysics Letters, 2015, 111, 64002.	2.0	11
29	Optical and structural characterization of CeO <sub>2</sub> /B <sub>4</sub> C multilayers near boron K-edge energy. , 2015, , .		0
30	Extreme ultraviolet proximity lithography for fast, flexible and parallel fabrication of infrared antennas. Optics Express, 2015, 23, 25487.	3.4	9
31	Analysis of buried interfaces in multilayer mirrors using grazing incidence extreme ultraviolet reflectometry near resonance edges. Applied Optics, 2015, 54, 10351.	2.1	4
32	Ptychographic imaging with a compact gas discharge plasma extreme ultraviolet light source. Optics Letters, 2015, 40, 5574.	3.3	24
33	Analysis of distinct scattering of extreme ultraviolet phase and amplitude multilayer defects with an actinic dark-field microscope. , 2015, , .		3
34	Employing partially coherent, compact gas-discharge sources for coherent diffractive imaging with extreme ultraviolet light. , 2015, , .		1
35	Interferometric broadband Fourier spectroscopy with a partially coherent gas-discharge extreme ultraviolet light source. Optics Letters, 2015, 40, 2818.	3.3	6
36	Irradiation of low energy ions damage analysis on multilayers. Proceedings of SPIE, 2015, , .	0.8	2

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37	Fractional Talbot lithography with extreme ultraviolet light. Optics Letters, 2014, 39, 6969.	3.3	14
38	Generation of circularly polarized radiation from a compact plasma-based extreme ultraviolet light source for tabletop X-ray magnetic circular dichroism studies. Review of Scientific Instruments, 2014, 85, 103110.	1.3	15
39	Scalability limits of Talbot lithography with plasma-based extreme ultraviolet sources. Journal of Micro/ Nanolithography, MEMS, and MOEMS, 2013, 12, 033002.	0.9	29
40	Tabletop coherent diffraction imaging with a discharge plasma EUV source. , 2013, , .		2
41	Diffraction-assisted extreme ultraviolet proximity lithography for fabrication of nanophotonic arrays. Journal of Vacuum Science and Technology B: Nanotechnology and Microelectronics, 2013, 31, 021602.	1.2	15
42	Laser triggered Z-pinch broadband extreme ultraviolet source for metrology. Applied Physics Letters, 2013, 102, 203504.	3.3	18
43	Imaging with plasma based extreme ultraviolet sources. Proceedings of SPIE, 2012, , .	0.8	1
44	Cross characterization of ultrathin interlayers in HfO <sub>2</sub> high-k stacks by angle resolved x-ray photoelectron spectroscopy, medium energy ion scattering, and grazing incidence extreme ultraviolet reflectometry. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2012, 30, 041506.	2.1	8
45	Broadband transmission masks, gratings and filters for extreme ultraviolet and soft X-ray lithography. Thin Solid Films, 2012, 520, 5080-5085.	1.8	30
46	Quantum Efficiency Determination of a Novel CMOS Design for Fast Imaging Applications in the Extreme Ultraviolet. IEEE Transactions on Electron Devices, 2012, 59, 846-849.	3.0	0
47	Time resolved EUV pump-probe microscopy of fs-LASER induced nanostructure formation. , 2011, , .		0
48	Actinic EUV-mask metrology: tools, concepts, components. , 2011, , .		1
49	EUV actinic mask blank defect inspection: results and status of concept realization. Proceedings of SPIE, 2011, , .	0.8	2
50	EUV Dark-Field Microscopy for Defect Inspection. AIP Conference Proceedings, 2011, , .	0.4	3
51	Performance benchmark of a gateable microchannel plate detector for extreme ultraviolet radiation with high temporal resolution. , 2011, , .		1
52	Defect inspection with an EUV microscope. , 2010, , .		5
53	Contributions to EUV mask metrology infrastructure. , 2010, , .		1
54	Spectral Sharpening Algorithm for a Polychromatic Reflectometer in the Extreme Ultraviolet. Applied Spectroscopy, 2010, 64, 401-408.	2.2	1

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55	Line image sensors for spectroscopic applications in the extreme ultraviolet. Measurement Science and Technology, 2009, 20, 105201.	2.6	4
56	Table-top reflectometer in the extreme ultraviolet for surface sensitive analysis. Applied Physics Letters, 2009, 94, .	3.3	21
57	XUV metrology: surface analysis with extreme ultraviolet radiation. Proceedings of SPIE, 2009, , .	0.8	2
58	Optimization of a gas discharge plasma source for extreme ultraviolet interference lithography at a wavelength of 11 nm. Journal of Applied Physics, 2009, 106, .	2.5	38
59	EUV microscopy for defect inspection by dark-field mapping and zone plate zooming. Journal of Physics: Conference Series, 2009, 186, 012030.	0.4	21
60	Two magnification steps EUV microscopy with a Schwarzschild objective and an adapted zone plate lens. , 2009, , .		4
61	Innovative approaches to surface sensitive analysis techniques on the basis of plasma-based off-synchrotron XUV/EUV light sources. , 2008, , .		2
62	High speed reflectometer for EUV mask-blanks. , 2005, 5835, 252.		1
63	High speed reflectometer for EUV mask-blanks. , 2005, , .		1
64	High-throughput EUV reflectometer for EUV mask blanks. , 2004, , .		6
65	Fundamentals and limits for the EUV emission of pinch plasma sources for EUV lithography. Journal Physics D: Applied Physics, 2004, 37, 3213-3224.	2.8	68
66	Status of EUV-lamp development and demonstration of applications. , 2004, 5374, 943.		8
67	Metrology tools for EUV-source characterization and optimization. , 2004, , .		7
68	Metrology tools for EUVL-source characterization and optimization. , 2003, , .		6
69	Update on the EUVL mask blank activity at Schott Lithotec. , 2003, , .		3
70	EUV emission from Kr and Xe capillary discharge plasmas. Journal Physics D: Applied Physics, 2002, 35, 219-227.	2.8	28
71	<title>Comparison of different source concepts for EUVL</title>. , 2001, 4343, 215.		18
72	Pinch Plasma Radiation Sources for the Extreme Ultraviolet. Contributions To Plasma Physics, 2001, 41, 589-597.	1.1	12

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73	X-ray lasing as a result of an induced instability in an ablative capillary discharge. Journal Physics D: Applied Physics, 2001, 34, 336-339.	2.8	17
74	Investigation of X-ray lasing in a capillary discharge. European Physical Journal Special Topics, 2001, 11, Pr2-103-Pr2-106.	0.2	1
75	A capillary discharge as a pseudo-Planck radiator in the vacuum ultraviolet. Plasma Sources Science and Technology, 1999, 8, 370-375.	3.1	7